

MAGNESIUM OXIDE SPUTTERING TARGET

ABSTRACT

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A sputtering target configured from a magnesium oxide sintered body, wherein a ratio of crystal grains of the magnesium oxide sintered body in which a number of pinholes in a single crystal grain is 20 or more is 50% or less. The present invention is a sputtering target configured from a magnesium oxide sintered
10 body in which the generation of particles during sputtering is less.

Fig. 1